

Microsystems Technology Office

Brief to MAYO Foundation



Mr. Zachary J. Lemnios, Director
Dr. John C. Zolper, Deputy Director

13 January 2004



To develop, imaginative, innovative and often high-risk research ideas offering a significant technological impact that will go well beyond the normal evolutionary developmental approaches; and to pursue these ideas from the demonstration of technical feasibility through the development of prototype systems.

-- DoD Directive 5105.15

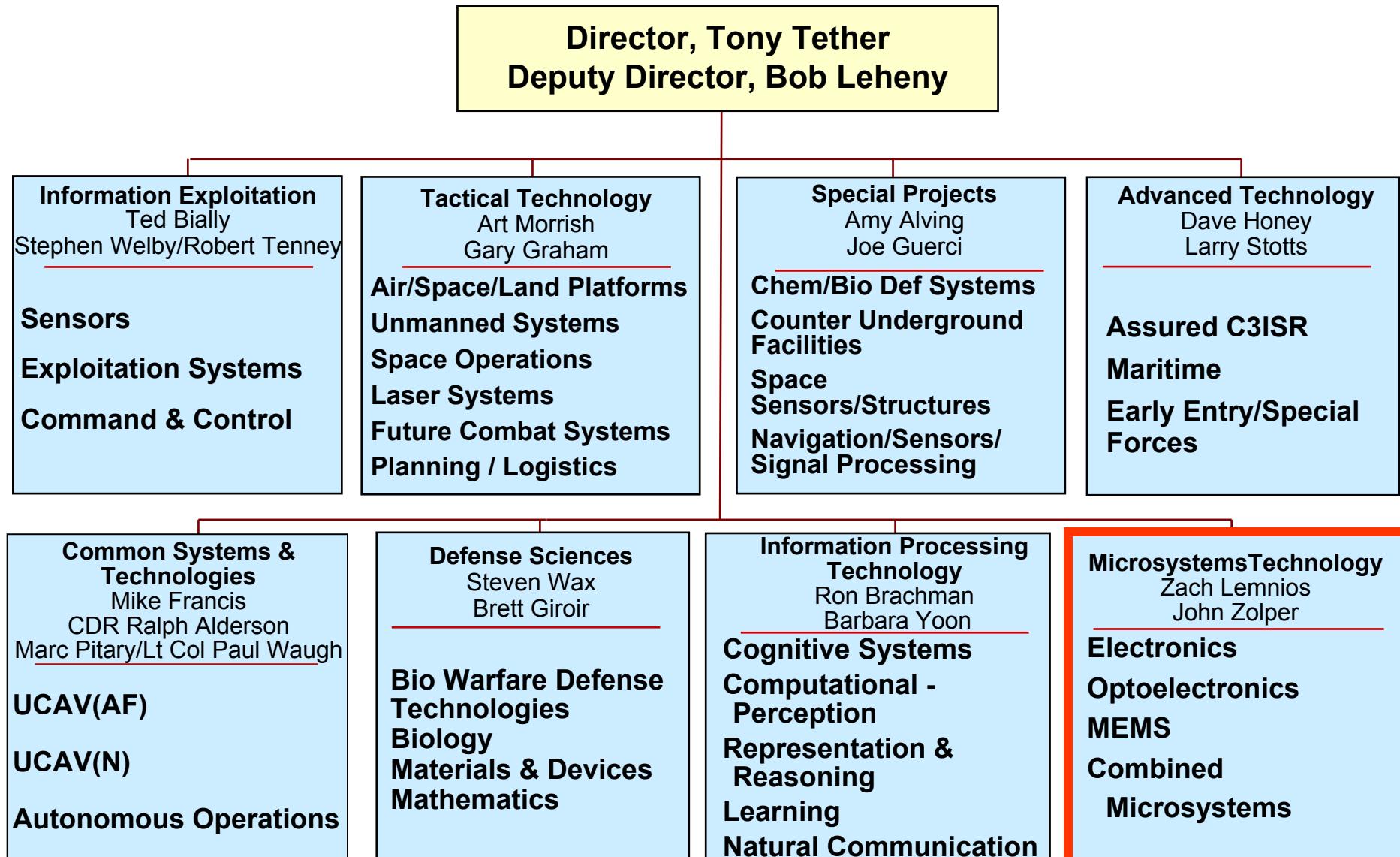
February 7, 1958



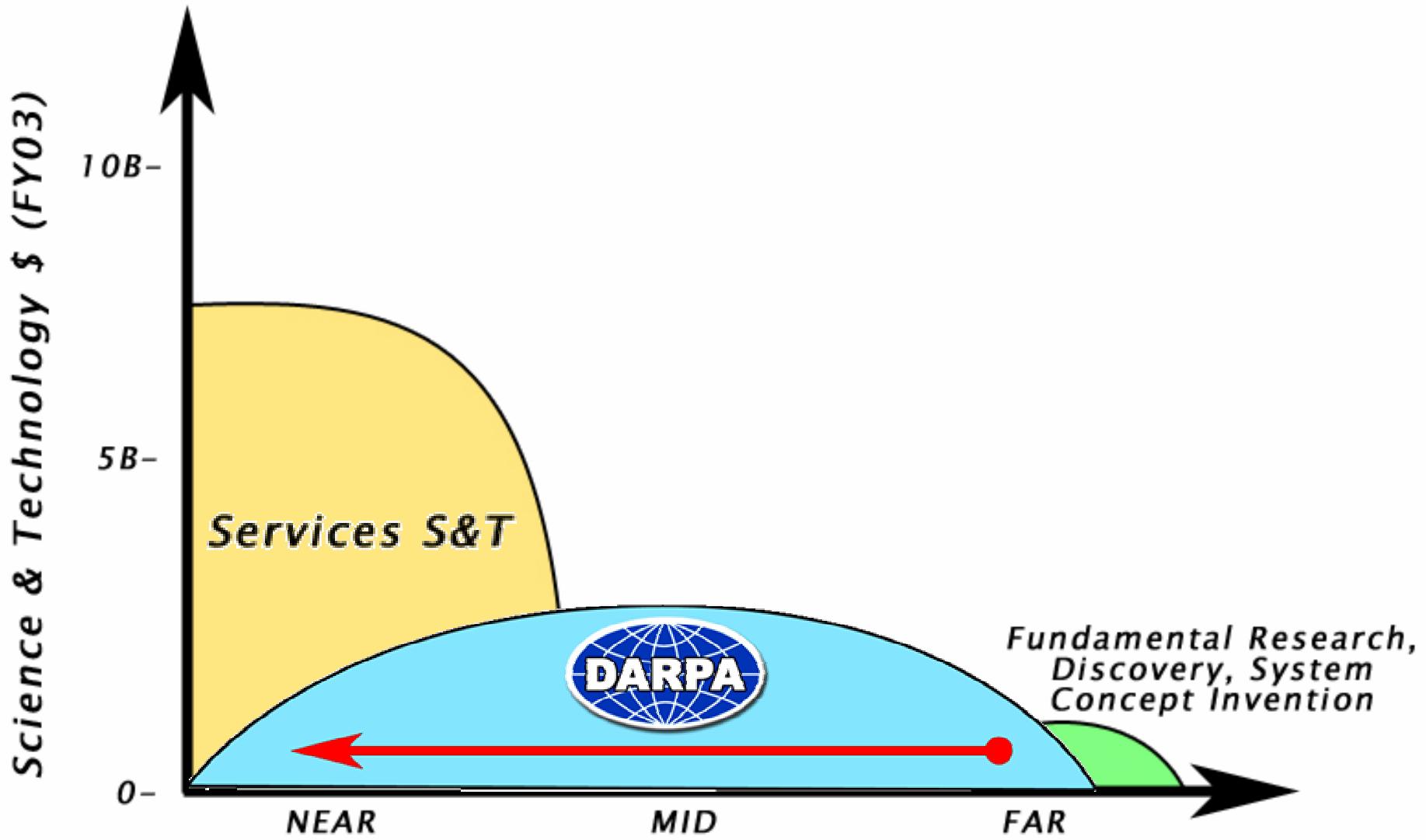
Outline



- • DARPA Overview
- MTO Thrusts
- Impact that MAYO has had on current MTO Programs



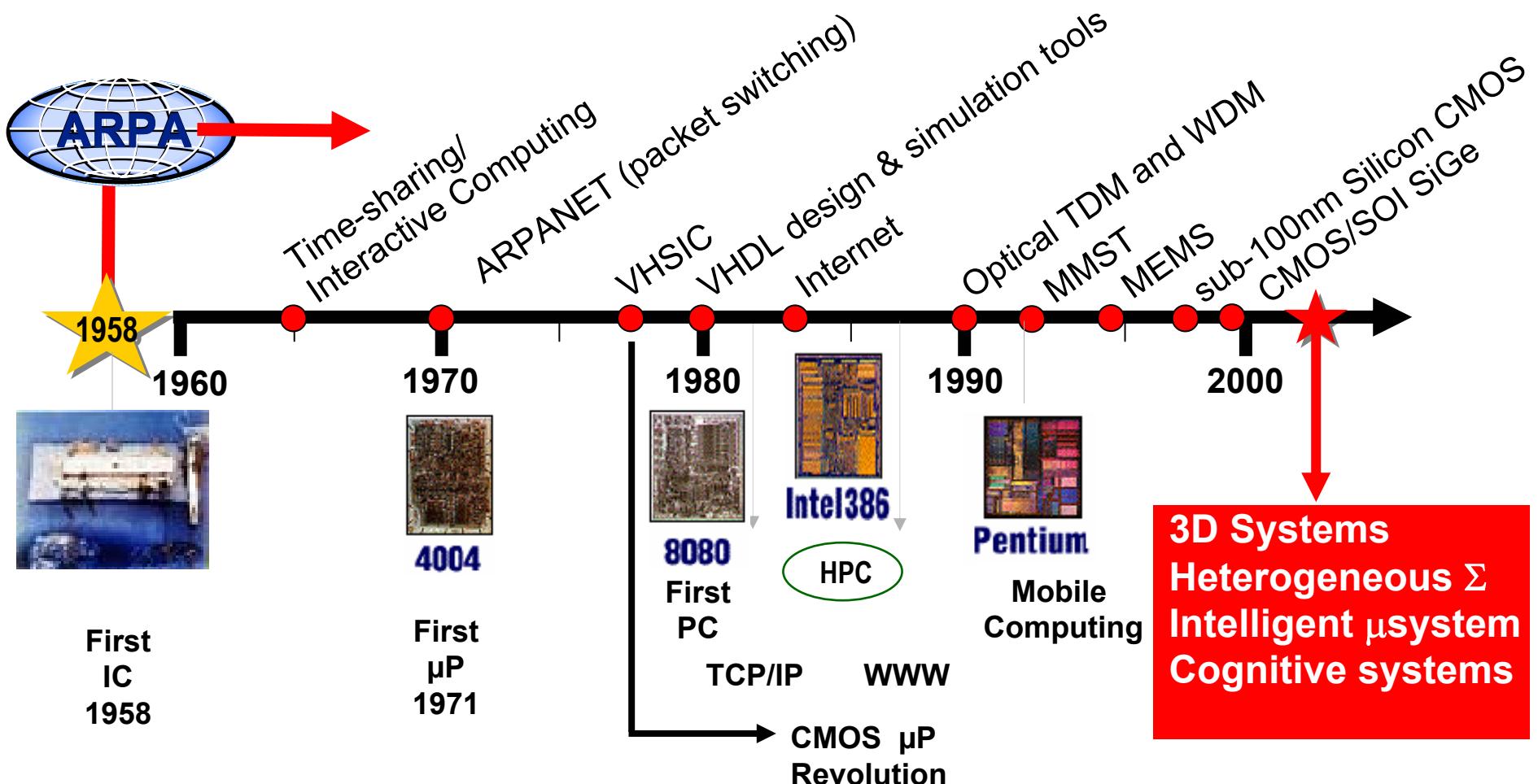
DARPA Role in Science and Technology



DARPA and the Computing Revolution



DARPA largely drove the information technology revolution of the second half of the 20th century





Outline



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Develop, demonstrate and transition the key solid state technologies that enable dominant system concepts and capabilities for the Department of Defense



Pushing the limits of scaling and integration



Microsystems for spectral exploitation and sensor dominance



Systems that intelligently interact with the environment



Tools that enable scalable and affordable access to leading edge components

DoD Access to Winning Microsystem Technology



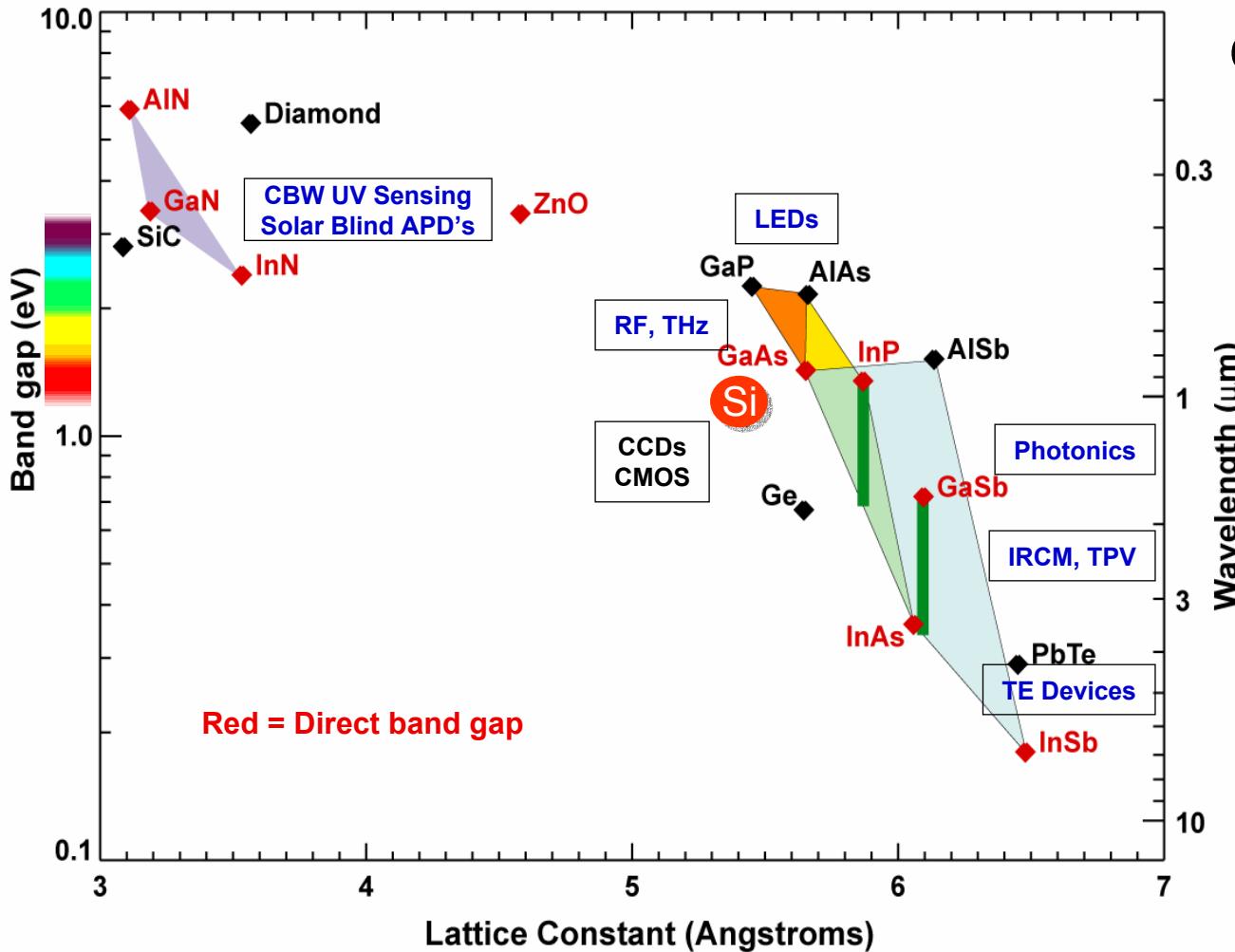
DARPA/MTO Technical Staff



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RF systems, deeply scaled CMOS, tech insertion
Semiconductor Materials, Devices, & Circuits
Short Pulse Lasers, Photonics / Sensors
Electronics- Materials, Devices & Circuits
Electronic & Photonic devices, Circuits & ICs
Lithography, Semiconductors, Materials
Photonic devices & materials
MEMS
Electronics / Heterogeneous Integration
Mathematics/Advanced Processing Algorithms
THz technology and high speed electronics
Photonic/Electronics RF links and comms
Molecular & Nano tech, Sub-atomic physics
Optical computing & interconnects, Imaging
Digital & intelligent imaging devices
Distributed robotics & Electro-textiles
Silicon microelectronics & flexible / macroelectronics
Photonic / Electronic device physics
Lasers, Sensors & Materials
MEMS

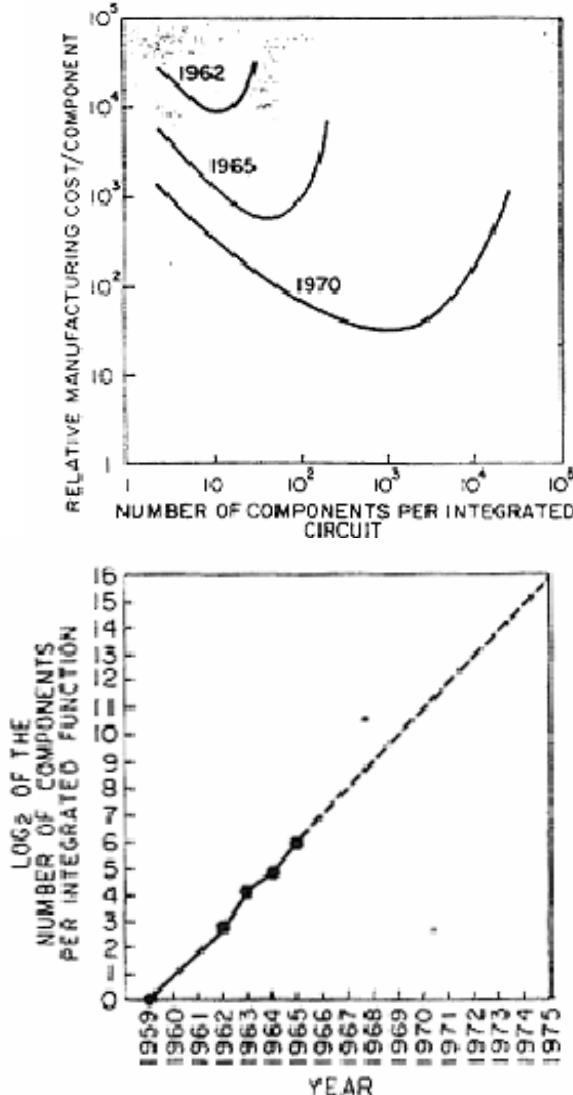
DoD's Need for Advanced Materials



Critical Applications

- IR detectors
- Thermophotovoltaic devices
- Solar blind UV detectors
- Lasers / LEDs
- Thermoelectric devices
- Optical waveguides and photonics
- THz Sources

1965 Publication of “Moore’s Law”



The experts look ahead

Cramming more components onto integrated circuits

With unit cost falling as the number of components per circuit rises, by 1975 economics may dictate squeezing as many as 65,000 components on a single silicon chip

By Gordon E. Moore

Director, Research and Development Laboratories, Fairchild Semiconductor division of Fairchild Camera and Instrument Corp.

The future of integrated electronics is the future of electronics itself. The advantages of integration will bring about a proliferation of electronics, pushing this science into many new areas.

Integrated circuits will lead to such wonders as home computers—or at least terminals connected to a central computer—automatic controls for automobiles, and personal portable communications equipment. The electronic wristwatch needs only a display to be feasible today.

But the biggest potential lies in the production of large systems. In telephone communications, integrated circuits in digital filters will separate channels in multiplex equipment. Integrated circuits will also switch telephone circuits and perform data processing.

Computers will be more powerful, and will be organized in completely different ways. For example, memories built of integrated electronics may be distributed throughout the

machine instead of being concentrated in a central unit. In addition, the improved reliability made possible by integrated circuits will allow the construction of larger processing units. Machines similar to those in existence today will be built at lower costs and with faster turn-around.

Present and future

By integrated electronics, I mean all the various technologies which are referred to as microelectronics today as well as any additional ones that result in electronics functions supplied to the user as irreducible units. These technologies were first investigated in the late 1950's. The object was to miniaturize electronics equipment to include increasingly complex electronic functions in limited space with minimum weight. Several approaches evolved, including microassembly techniques for individual components, thin-film structures and semiconductor integrated circuits.

Each approach evolved rapidly and converged so that each borrowed techniques from another. Many researchers believe the way of the future to be a combination of the various approaches.

The advocates of semiconductor integrated circuitry are already using the improved characteristics of thin-film resistors by applying such films directly to an active semiconductor substrate. Those advocating a technology based upon films are developing sophisticated techniques for the attachment of active semiconductor devices to the passive film array.

Both approaches have worked well and are being used in equipment today.



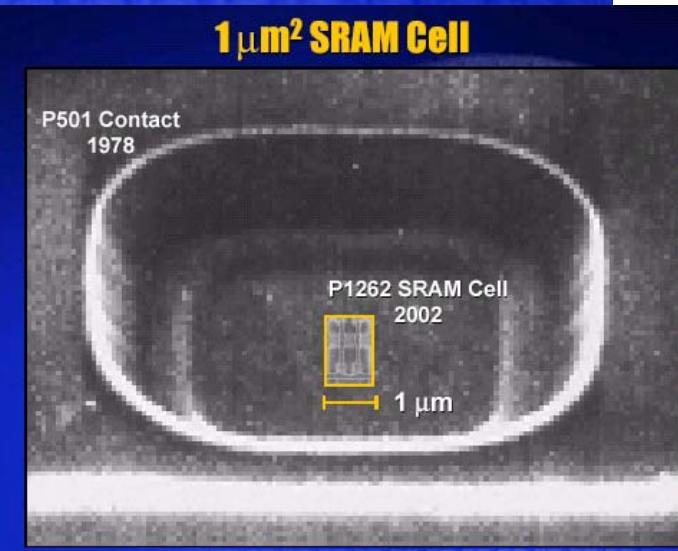
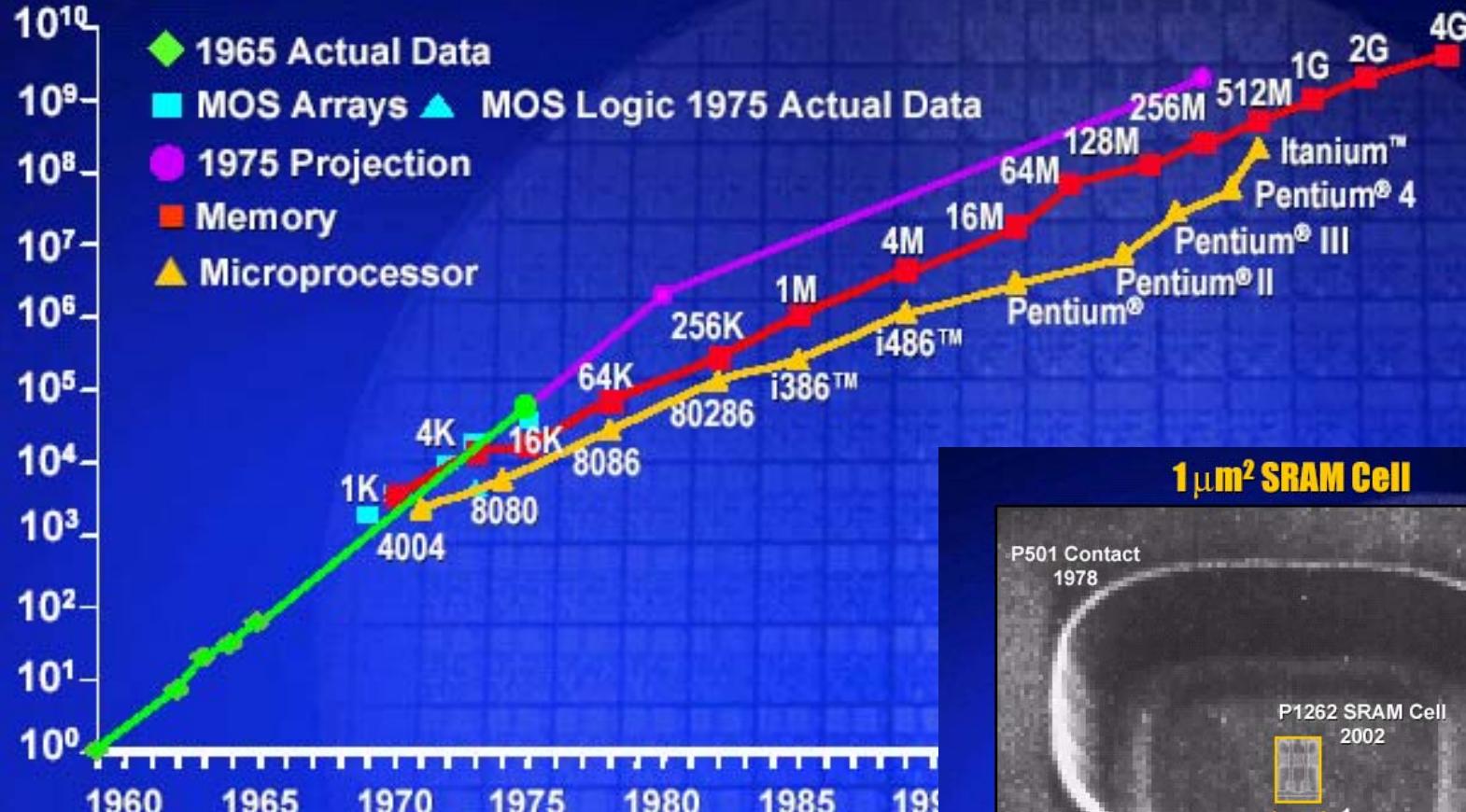
Dr. Gordon E. Moore is one of the new breed of electronic engineers, a crossbred in the physical sciences rather than in electronics. He earned a B.S. degree in chemistry from the University of California and a Ph.D. degree in physical chemistry from the California Institute of Technology. He was one of the founders of Fairchild Semiconductor and has been director of the research and development laboratories there since 1959.

Electronics, Volume 38, Number 8, April 19, 1965

Moore's Law Scaling

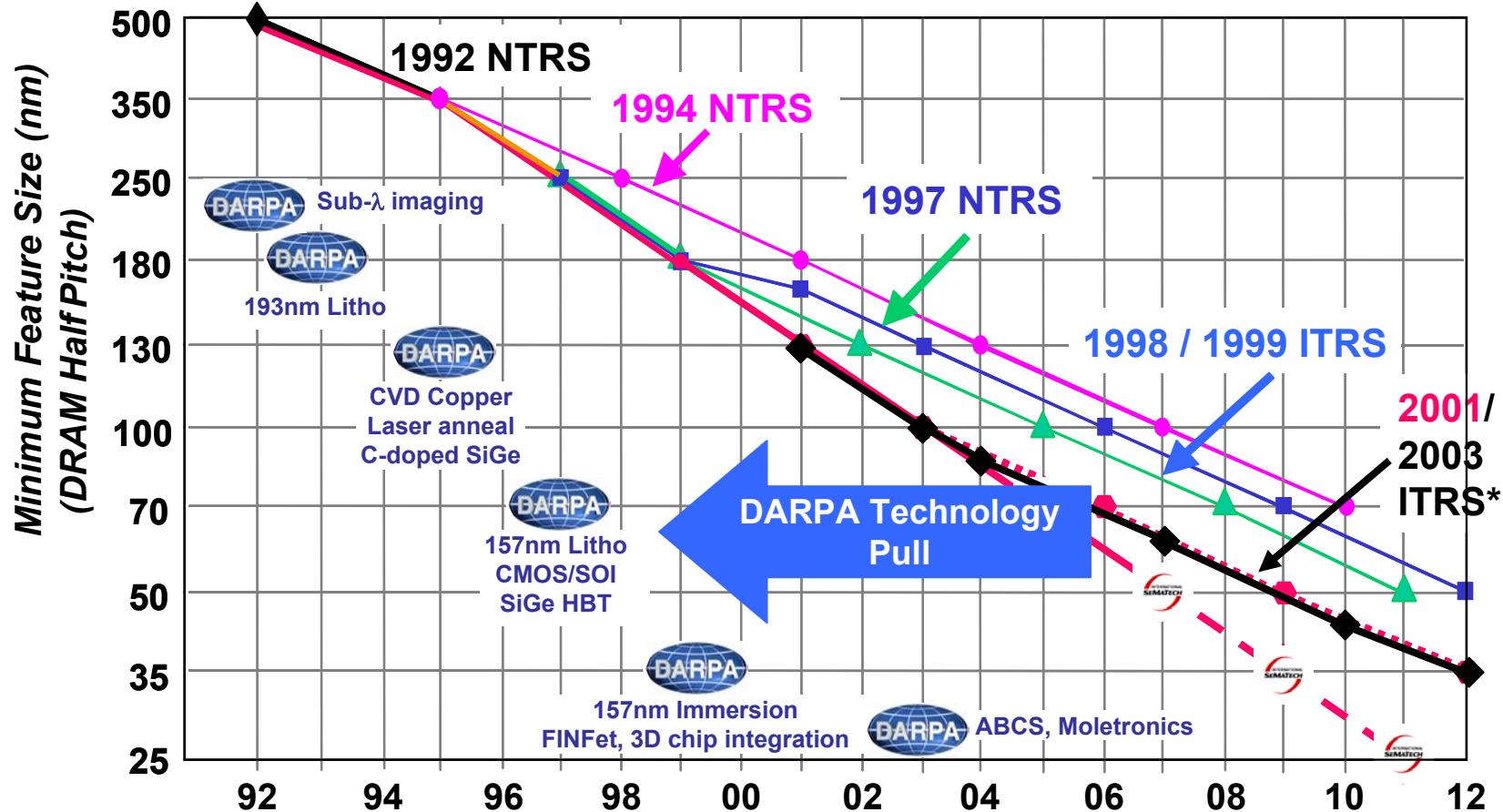
Transistors

Per Die

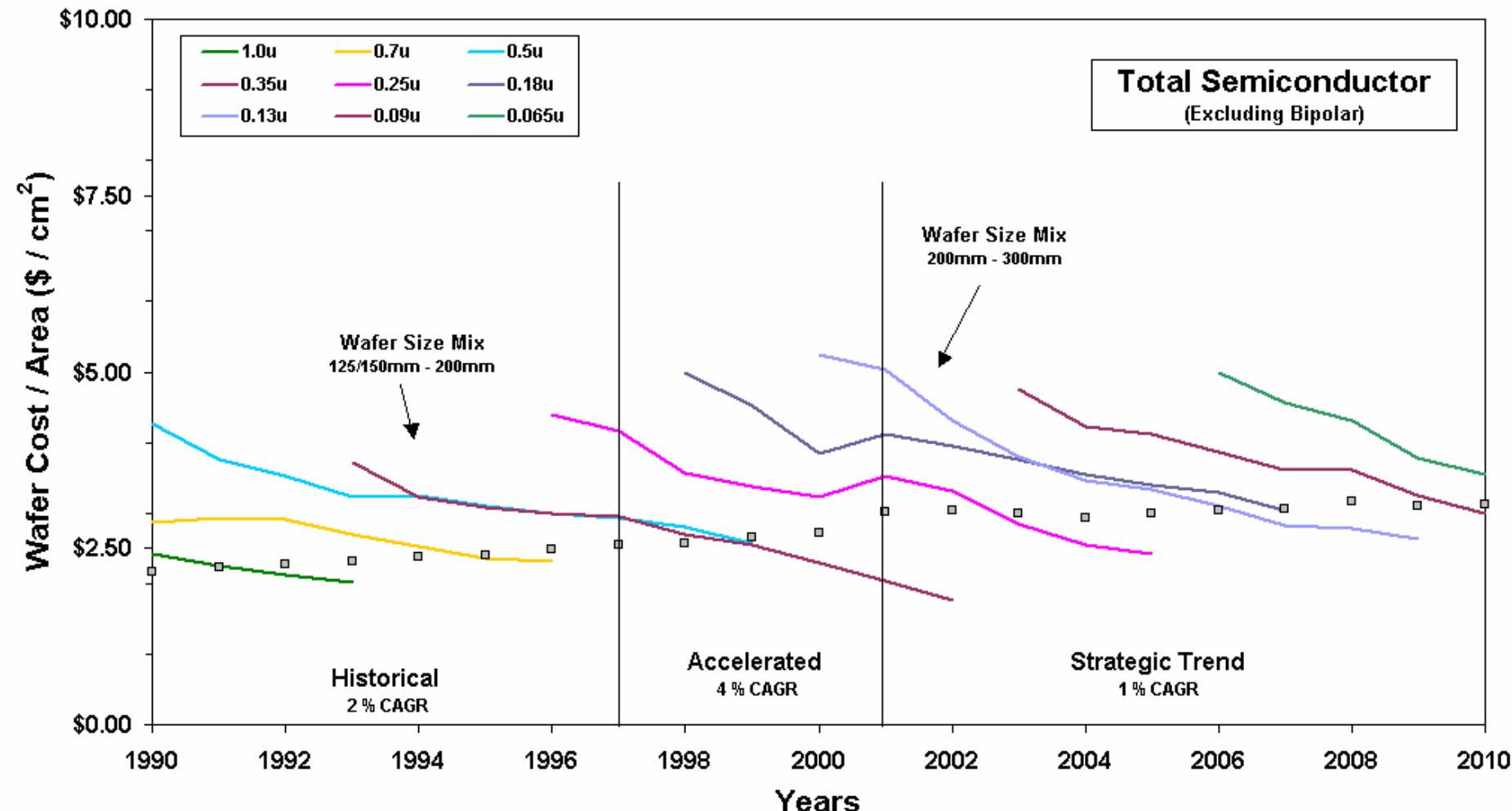


From Peter Asbeck

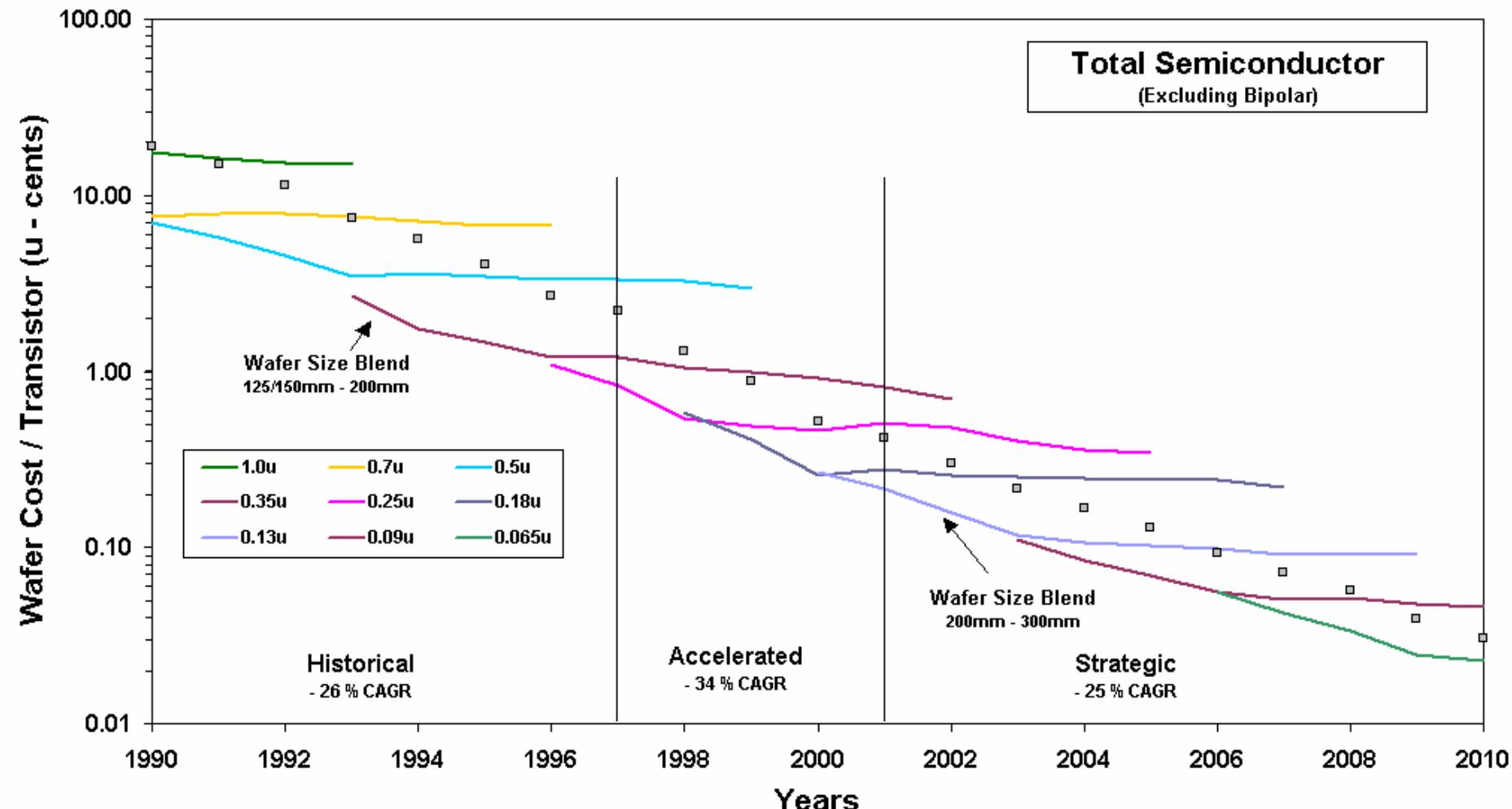
Technology Roadmap



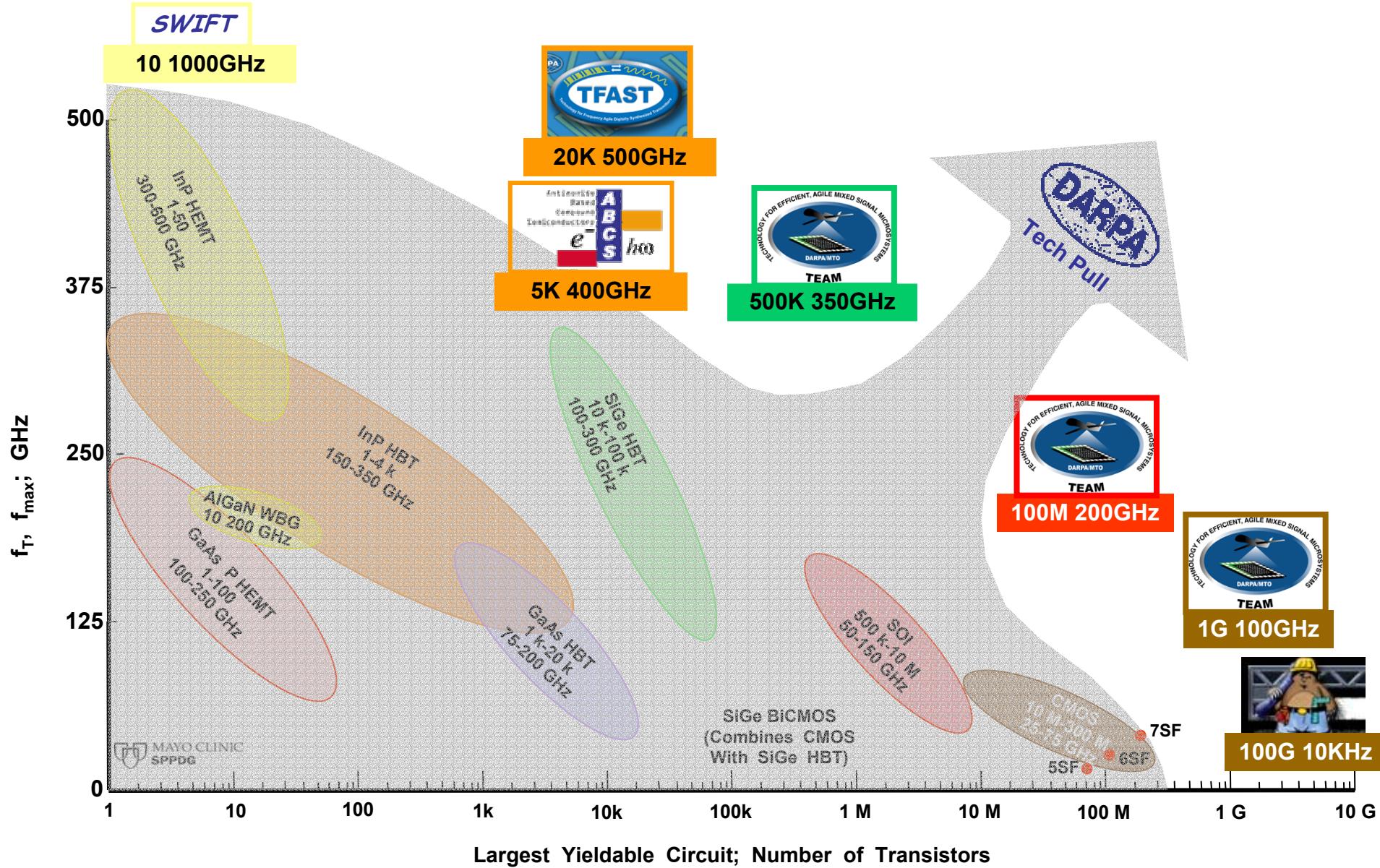
Constant Wafer Cost / Area



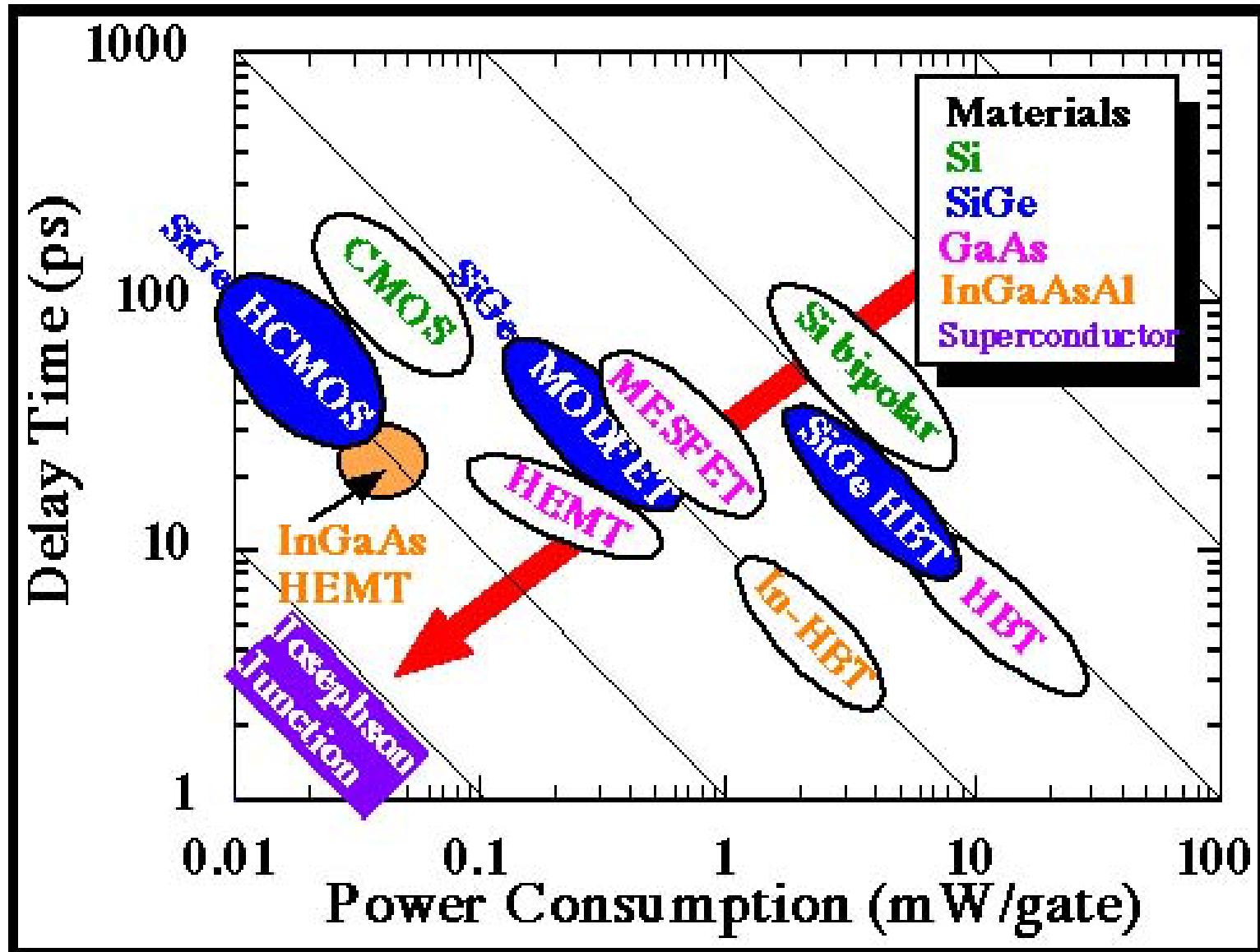
Commercial CMOS Productivity Engine



Integrated Ft Device Scaling



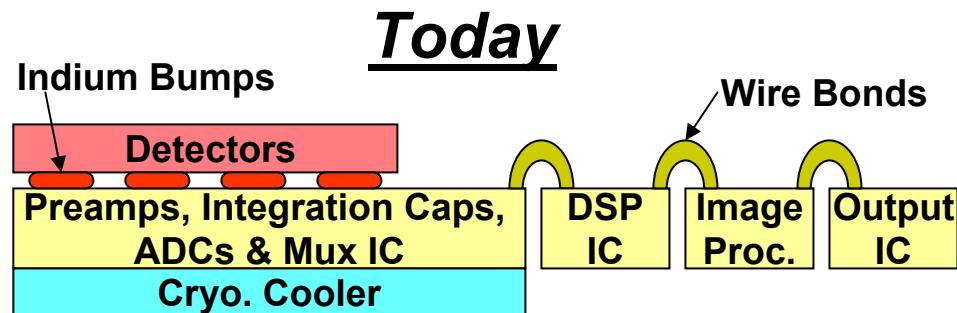
Power Gate Delay Chart



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Vertically Interconnected Sensor Arrays (VISA)

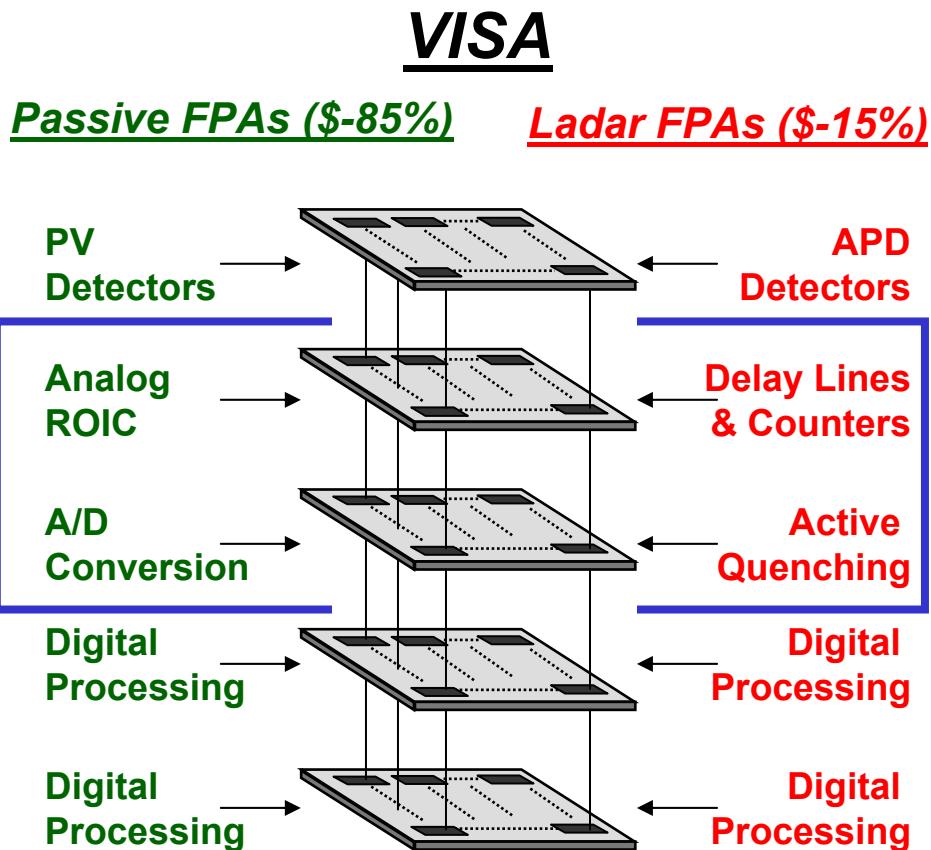


For Passive IRFPAs

- Low Frame Rates
(Serial read out (<0.3kHz))
- Narrow Dynamic Range
(capacitor/pixel limited (12-bits max.))
- ROIC-limited array format

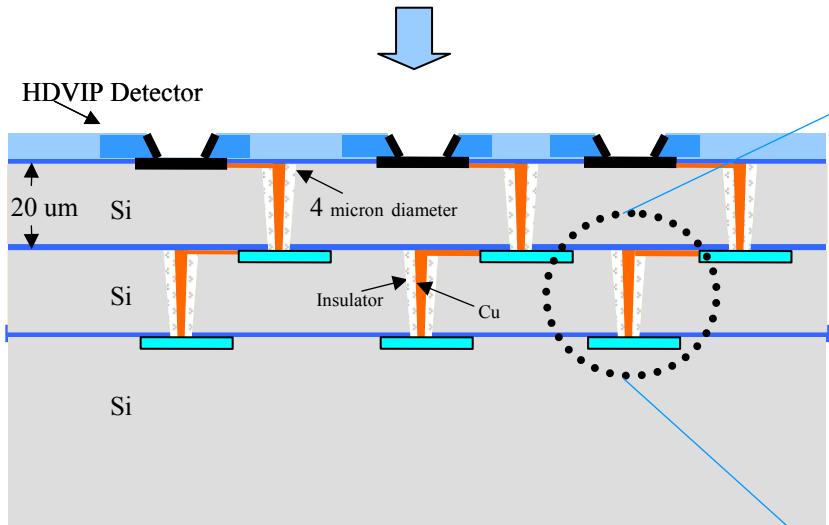
For Ladar FPAs

- Large Pixel Sizes ($100\mu \times 100\mu$)
- Low Sampling Rates (1.0GHz)

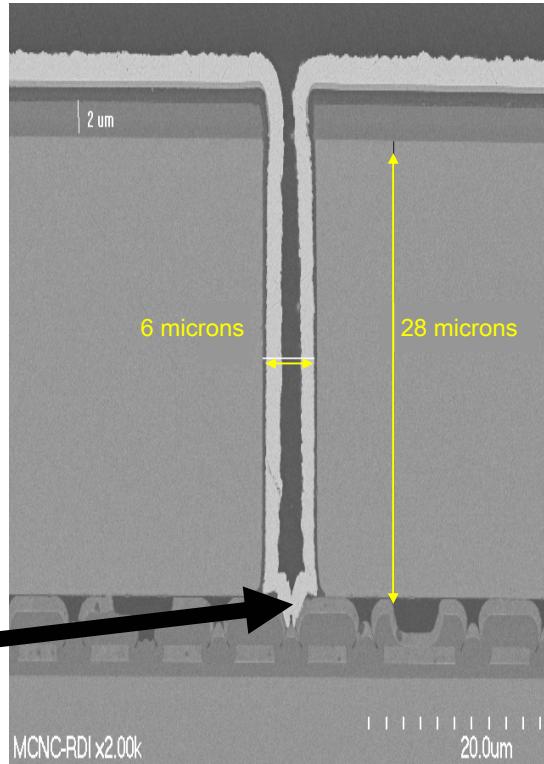


- High Pixel Access Rates (up to 100MHz)
- Wide Dynamic Range (>20-bits)
- Reduced Ladar Pixel Sizes ($30\mu \times 30\mu$)
- High Ladar Sampling Rates (10GHz)

VISA Process Feasibility Demonstrated

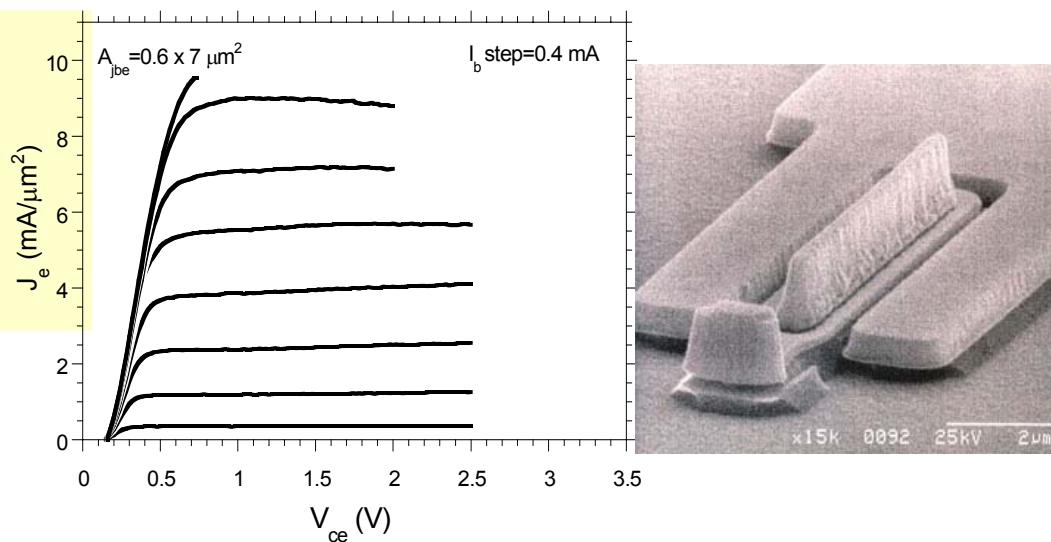
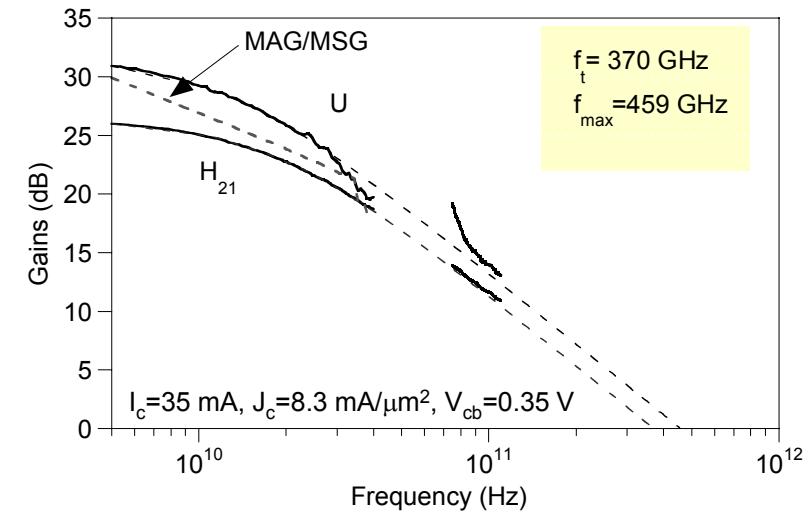


Note contact between vertical
Interconnect and bottom metal pad !



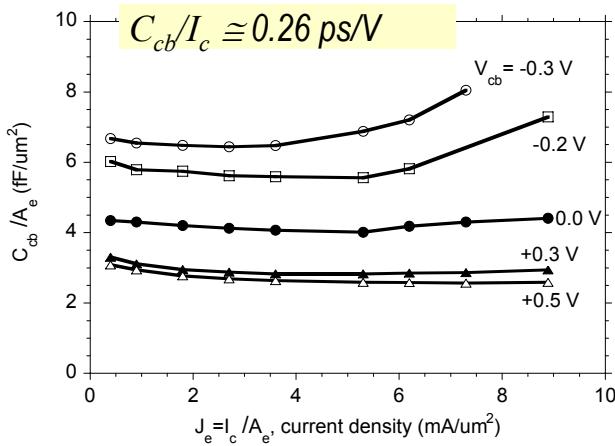
**Feasibility of VISA interconnect process has been demonstrated.
Refinements to improve operability and yield now in progress.**

InP DHBTs: 150 nm collector, 30 nm base



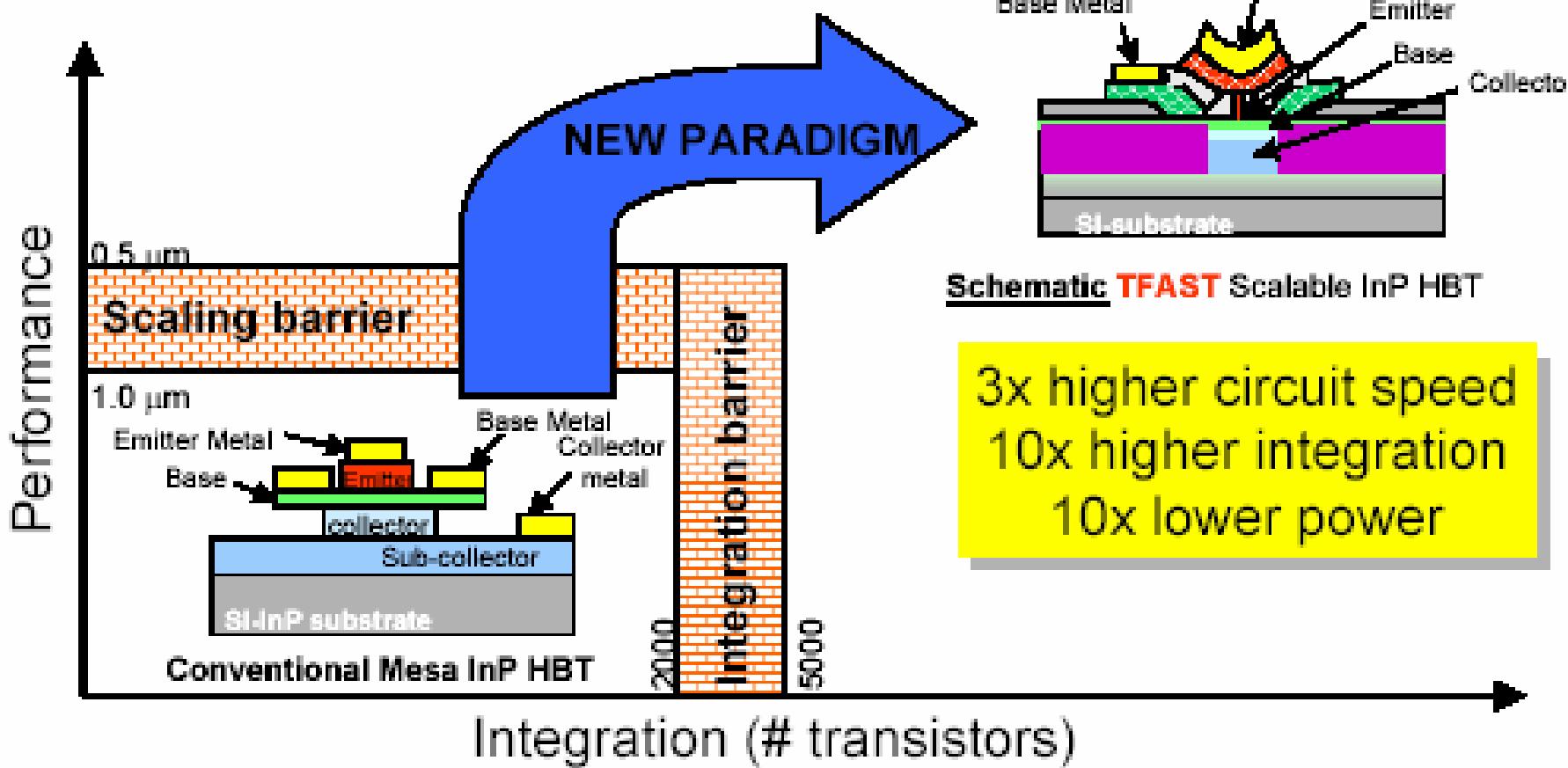
3 nm InGaAs base: $8 \times 10^{19}/\text{cm}^3 \rightarrow 5 \times 10^{19}/\text{cm}^3$
 15 nm InP collector
 0.6x 7 μm emitter junction (0.7 x 8 um contact)
 0.5 μm base contacts

base: $603 \Omega/\text{square}$
 base contacts: $20 \Omega \cdot \mu\text{m}^2$
 emitter contacts: $15 \Omega \cdot \mu\text{m}^2$



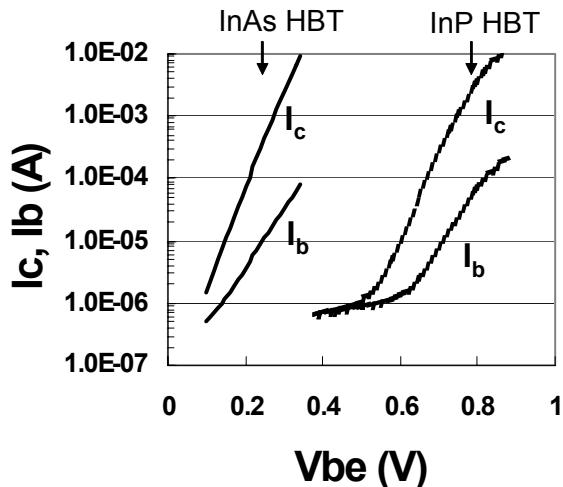
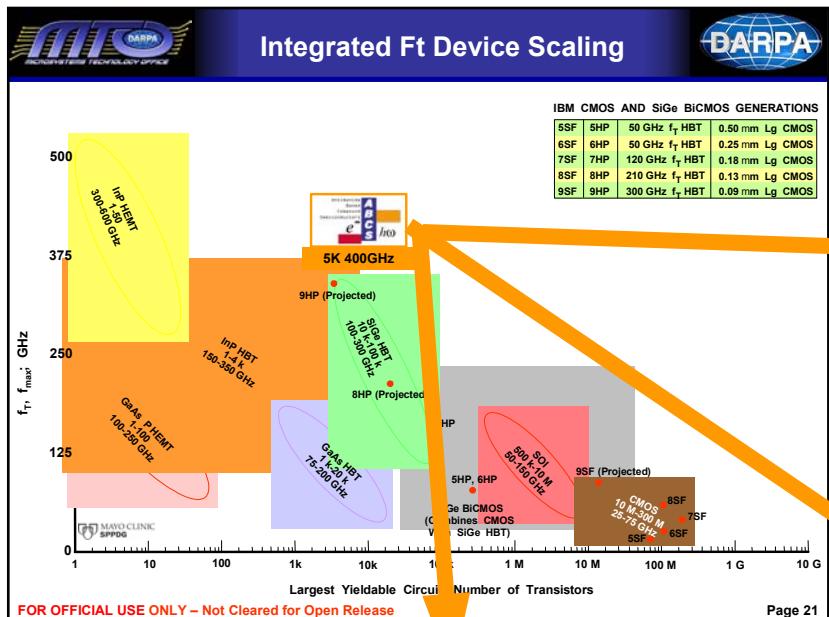
Thickness (Å)	Material	Doping cm ⁻³	Description
400	In _{0.53} Ga _{0.47} As	3E19 : Si	Emitter Cap
800	InP	3E19 : Si	Emitter
100	InP	8E17 : Si	Emitter
300	InP	3E17 : Si	Emitter
300	InGaAs	8E19-5E19:C	Base
200	In _{0.53} Ga _{0.47} As	3E16:Si	Setback
240	InGaAlAs	3E16 : Si	Base-Collector Grade
30	InP	3.0E18 : Si	Delta doping
1000	InP	3E16 : Si	Collector
250	InP	1.5E19:Si	Sub Collector
125	In _{0.53} Ga _{0.47} As	2E19 : Si	Sub Collector
3000	InP	2E19 : Si	Sub Collector
Substrate	SI : InP		

InP HBT Technology Being Redefined by TFAST

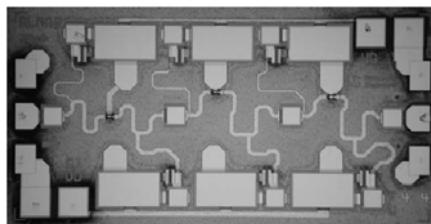
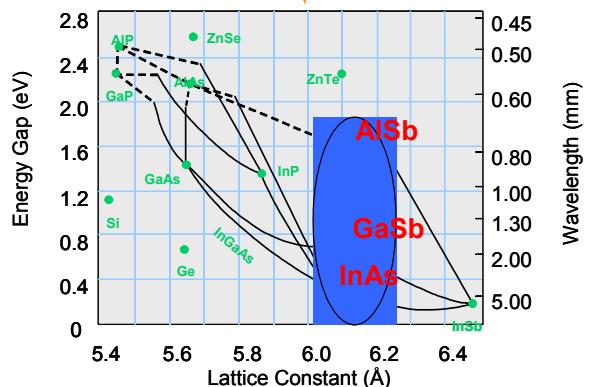


Antimonide-based Compound Semiconductor (ABCS)

Exploiting Antimonide Materials for High Speed at Low Power

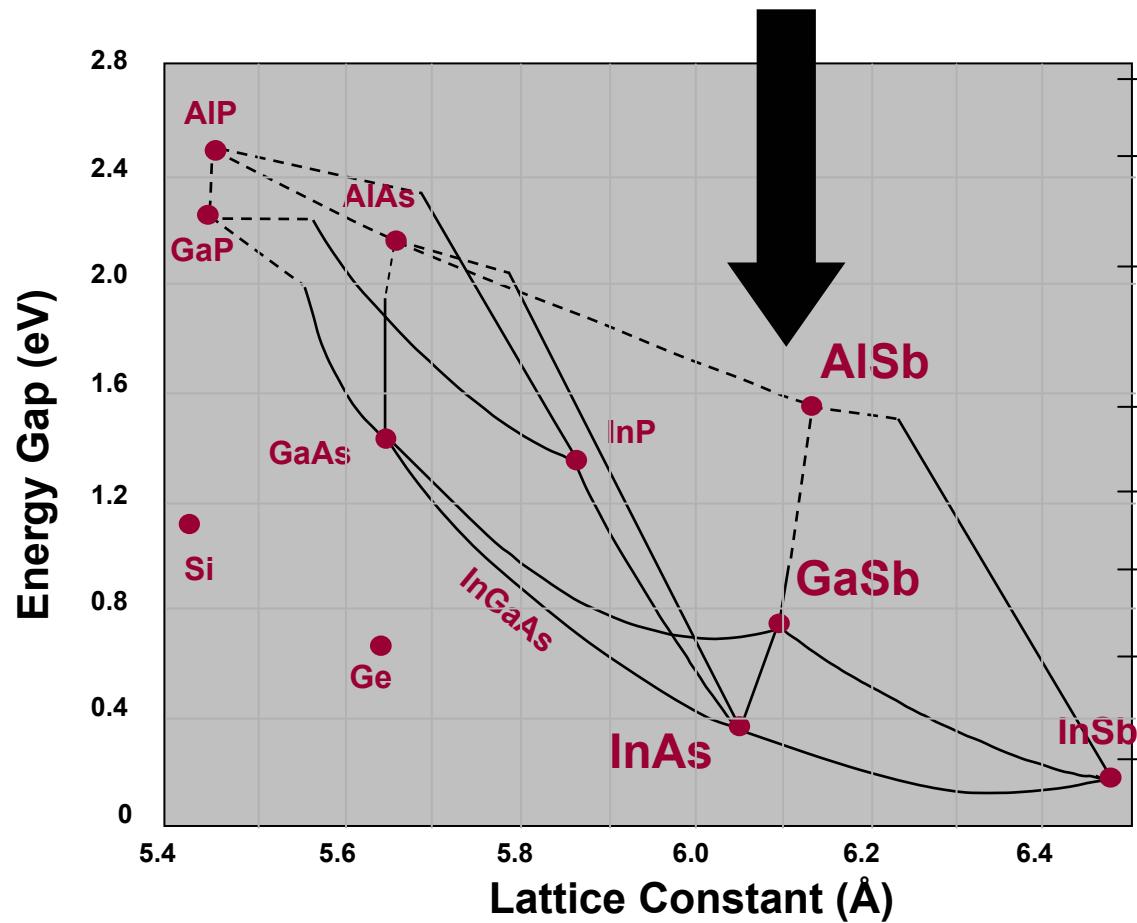


ABCS InAs-HBT Operates at Low Voltage

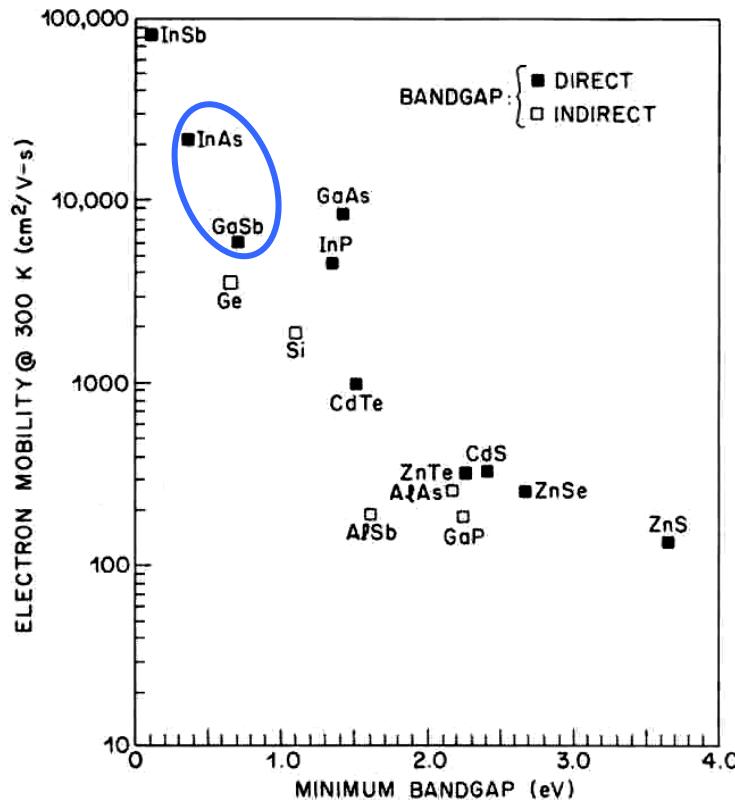


34-36 ABCS Low Noise Amplifier
NF = 2.1 F, P_{dis} = 4.5 mW
>10 X lower power than InP PHEMT

6.1 Å III-V Materials

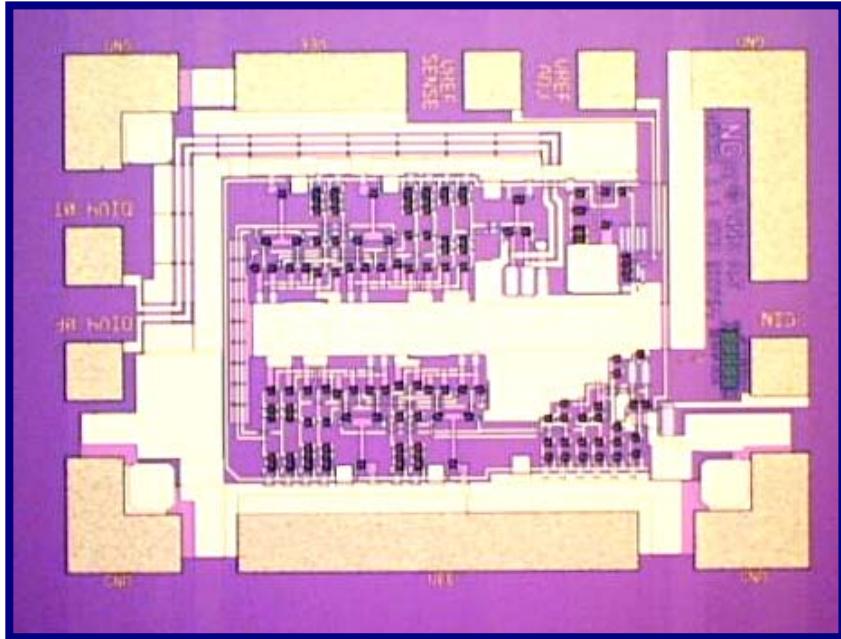


Electron Mobility



The main focus of the ABCS program is to demonstrate integrated circuits with ultrafast speed and low consumed power

ABCS LNA Circuit Development



$F_{clock} = 21.2 \text{ GHz}$

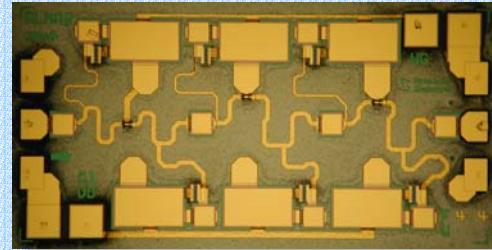
$F_{output} = 5.3 \text{ GHz}$

High InAs / AlSb MMIC Integration

Demonstrated a divide by 4 circuit with ~ 100 HBTs operating at $f_{clock} = 21.2 \text{ GHz}$

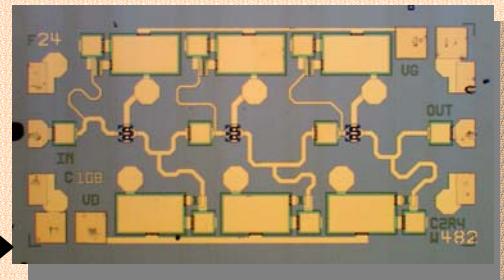
ABCS

Ka-Band LNA
0.35V, 12mA Fets
Gain = 28dB
NF < 2.2 dB
Power = 4.2mW



GaAs

Ka-Band LNA
4V, 40mA Fets
Gain = 20 - 27dB
Power = 160 mW

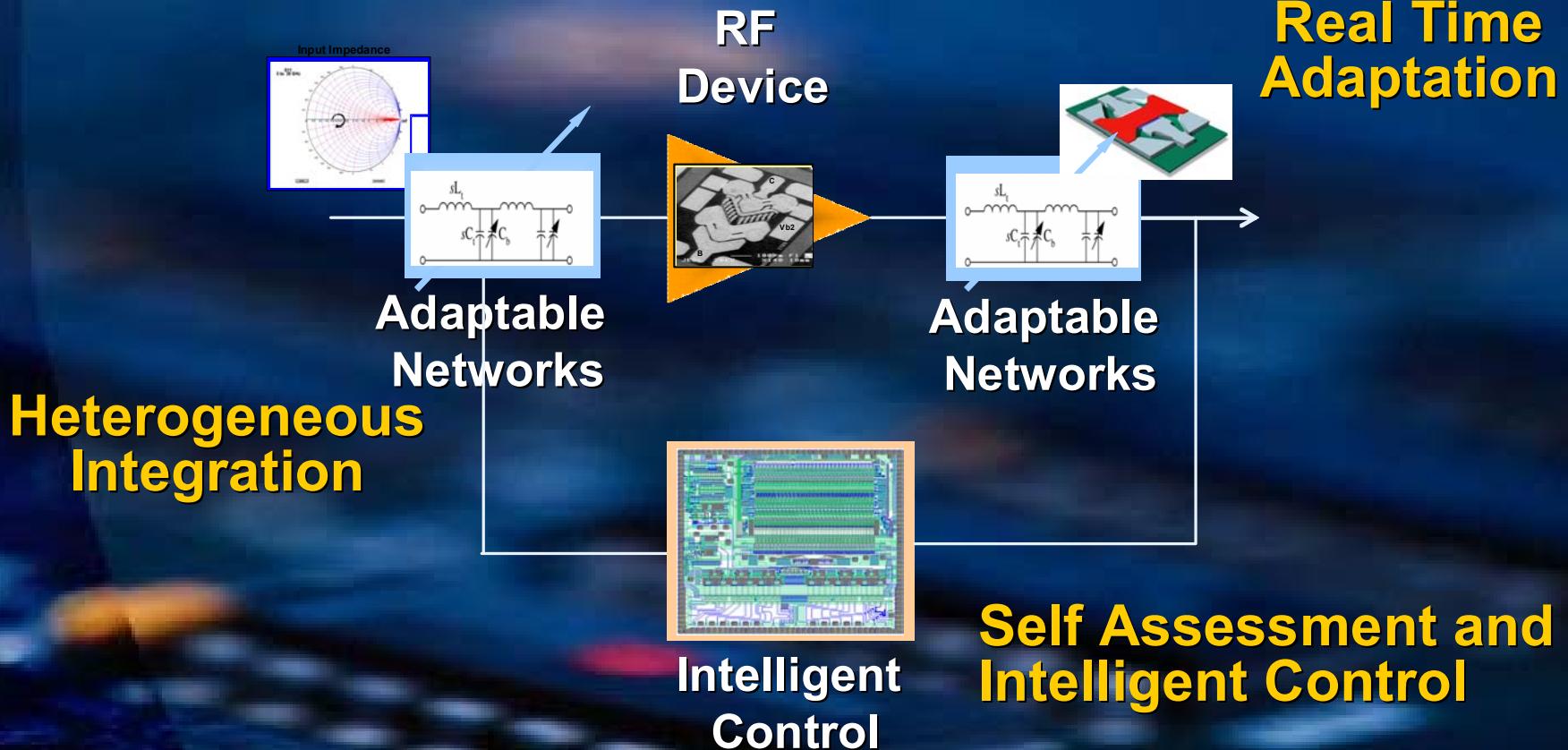


Part currently used in PAC-3

World's First InAs / AlSb MMICs

3-Stage Ka-Band LNA Using only 4.2 mW DC Power
~40 X Less Power than GaAs with Equivalent Performance

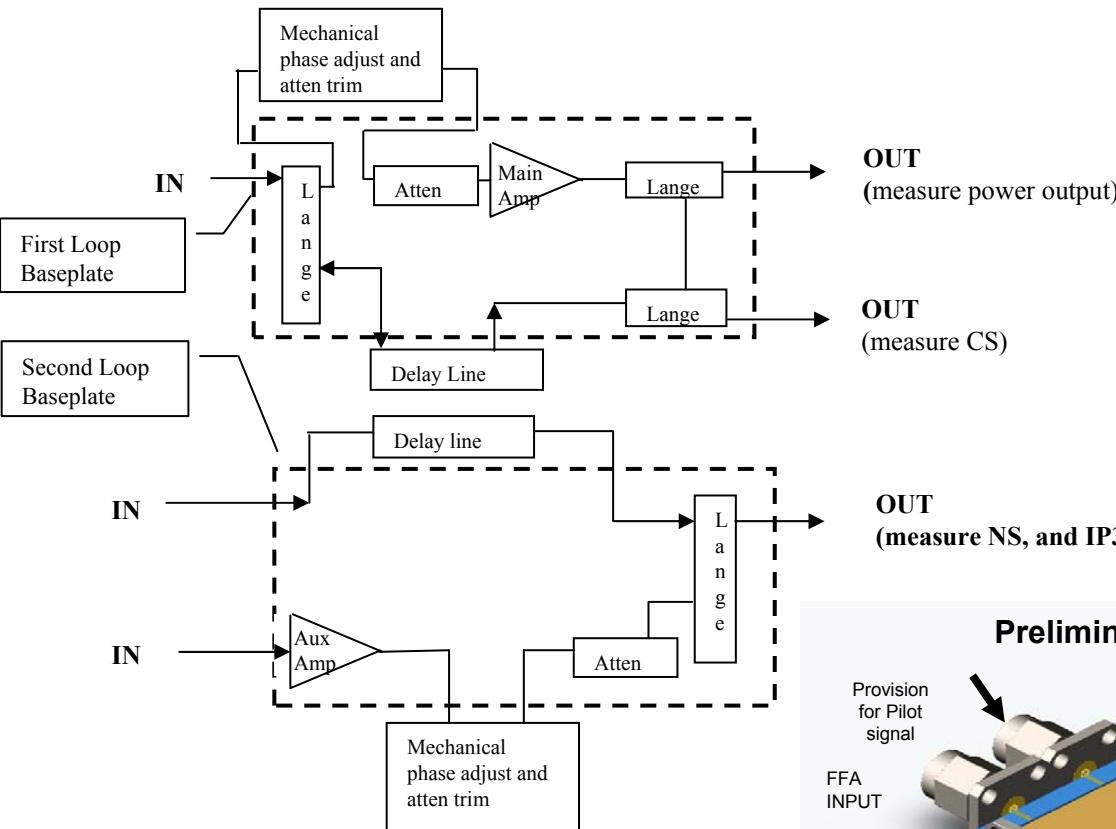
Intelligent RF Front Ends



Enabling Adaptive Multifunctional RF Sensors
for Rapid Changing Environments

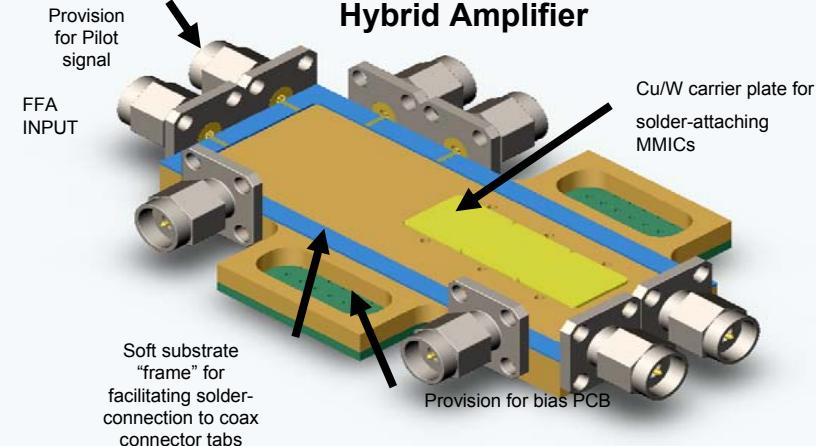
X-band Feedforward Amplifier (FFA) Development

Component Layout for Hybrid FFA

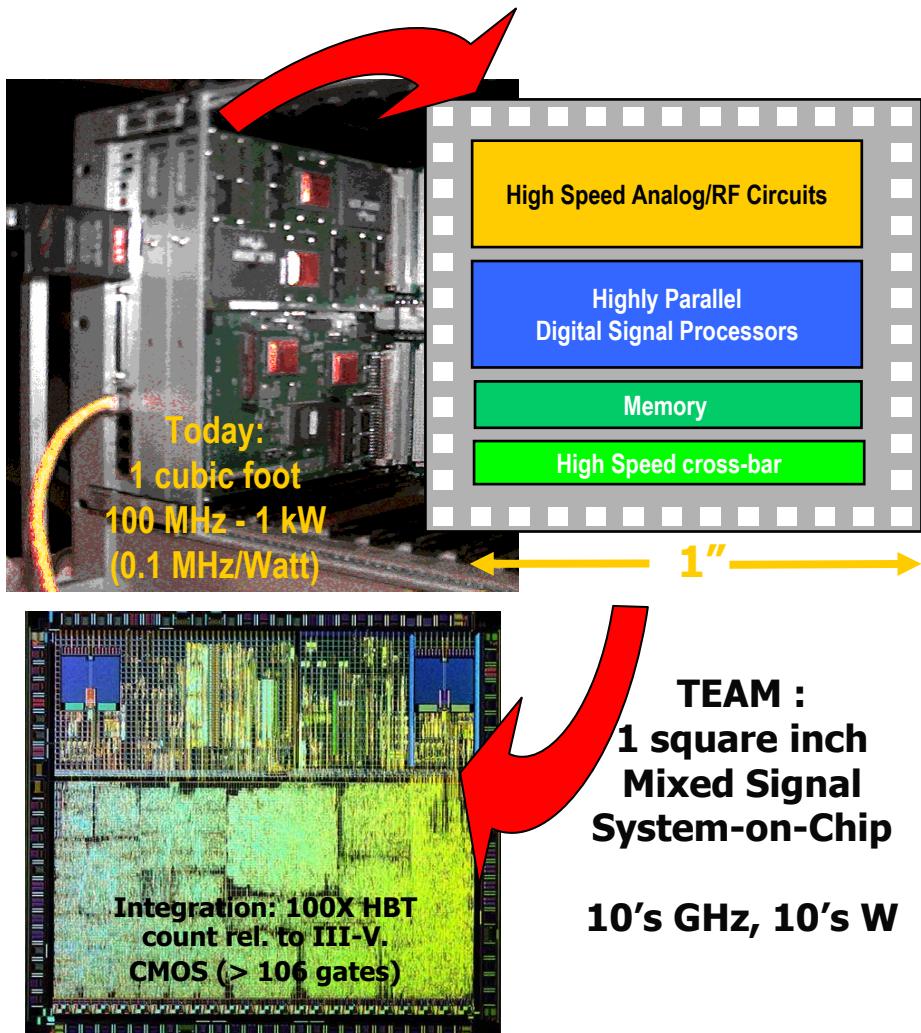


- Initial FFA design being implemented
 - Chip set procured (in-house) including a 2.8 W GaAs PHEMT MMIC amplifier from TriQuint for main amplifier
 - Cu/W carrier plates (for TCE match to GaAs) procured (in-house)
 - Custom collets (for solder die-attach) procured (in-house)
 - Beginning to set up solder die-attach experiments with mechanical samples
 - Coupler designs in progress; sample couplers on alumina in-house
 - Base-plate mechanical drawings in progress (first loop and 2nd loop hybrid circuit)

Preliminary Drawing of “First Loop”
Hybrid Amplifier



Technology for Efficient, Agile Mixed Signal Microsystems (TEAM)



Goal:

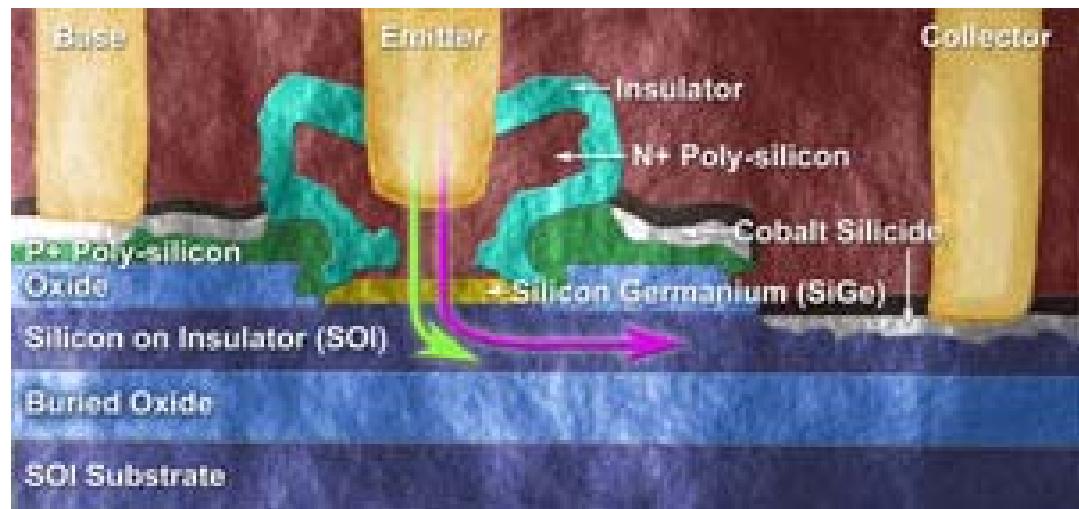
Demonstrate silicon (SiGe) devices with $f_t > 200\text{GHz}$ in low power circuits operating at up to 60GHz that deliver III-V device performance @ integration levels of 10K analog/RF devices & with submicron CMOS capable of > 10M transistors/chip to provide advanced, single chip RF systems

Challenges:

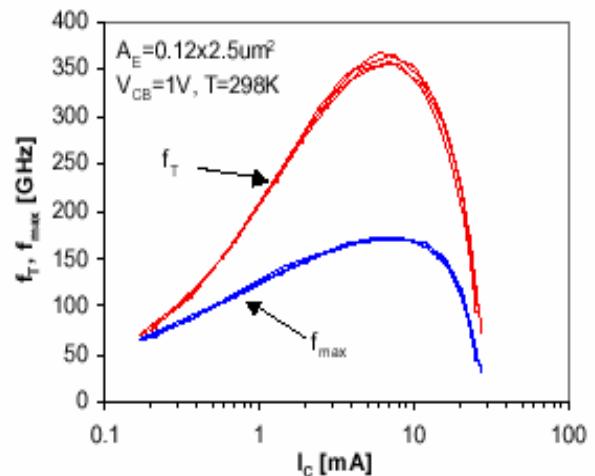
- High f_T , high gain silicon devices with low output conductance, low noise figure (<2dB @ 20GHz), high linearity and low power dissipation
- Techniques to achieve isolation between RF and digital blocks (~ 100dB) and on-chip Qs of >20
- Device integration levels for complex, single chip RF systems

Integrated chip-scale radar & radio transceivers with high performance, real time signal processing

Extending Si-based Transistors to >200 GHz Operation

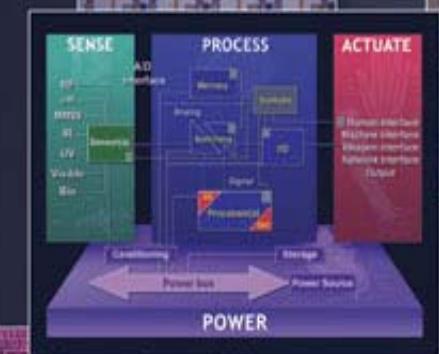


Cross-section of SiGe SHBT

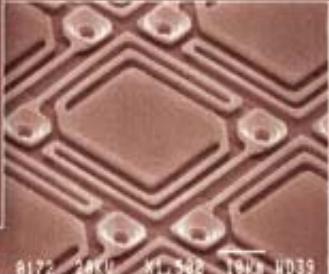
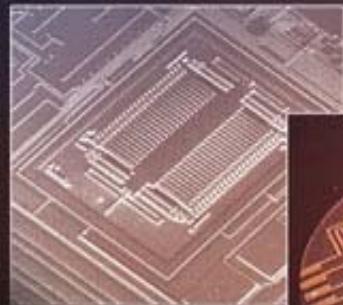


350 GHz IBM 0.12 μm SiGe SHBT

*Scalable and affordable access
to leading edge components*

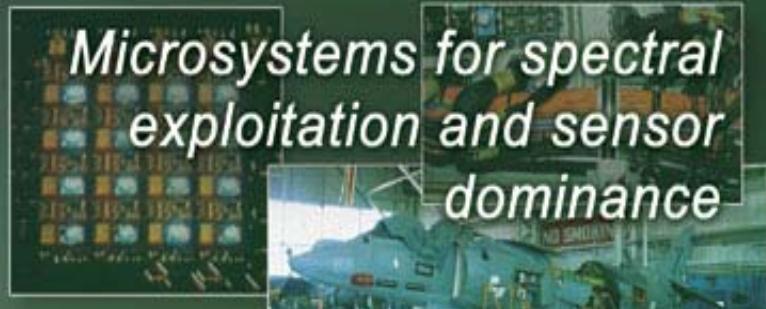


DoD Access to Winning Microsystem Technology



*Pushing the limits of
scaling and integration*

*Microsystems for spectral
exploitation and sensor
dominance*



*Systems that interact
with the environment*